

U.S. Patent Application No. 09/823,196

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE****RECEIVED  
CENTRAL FAX CENTER****AUG 26 2004****In re United States Patent Application of:****Applicants:** Thomas H. Baum, et al.**Group Art Unit:** 1621**Serial No:** 09/945,831**Examiner:** Nazario Gonzalez,  
Porfirio**Date Filed:** September 18, 2001**Confirmation No.:** 8827**Title:** Source Reagent Compositions for CVD  
Formation of Gate Dielectric Thin Films Using Amide  
Precursors and Method of Using Same**Customer No.:** 25559**FACSIMILE TRANSMISSION CERTIFICATE**

It hereby is certified by the person identified below that this paper is being facsimile transmitted by such person to the Commissioner of Patents and Trademarks on the date specified, to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, and Transmitted by Facsimile under the provisions of 37 CFR 1.6(d).

  
Maggie Chappuis

August 26, 2004  
Date of Transmission

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**AMENDMENT RESPONDING TO FEBRUARY 26, 2004 OFFICE ACTION IN U.S.  
PATENT APPLICATION NO. 09/954,831 AND PETITION FOR EXTENSION OF TIME  
UNDER 37 C.F.R. § 1.136**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

This responds to the February 26, 2004 Office Action in the above-identified application. Please amend the application as set out in the following **Section I** (Amendment of the Claims). Remarks addressing the substance of the February 17, 2004 Office Action are set out in **Section II** (Remarks) hereof.